

SYSTEM AND METHOD FOR ETCHING RESIN WITH AN OZONE WET ETCHING PROCESS

ABSTRACT OF THE INVENTION

5 A method is provided for cleaning resin residue in liquid
crystal display (LCD) or integrated circuit (IC) fabrication process.
The method comprises: forming an electrode layer; forming an
interlayer film of resin overlying the electrode later; patterning the
resin interlayer; forming a via to access the first area of the electrode
10 layer; in response to forming the via, forming a resin residue overlying
a first area of the electrode layer; introducing a gas mixture including
ozone into water to create a moist ozone gas, where the gas mixture is
approximately 10 % ozone by molecular weight (wt %); wet ashing the
resin residue overlying the first area of the electrode layer using the
15 moist ozone gas; and, depositing a metal layer overlying the first area
of the electrode to form a pixel electrode.